

suppressing the activity of the surface of the glass substrate 1G after performing "the second polishing step" in the method for manufacturing a glass substrate shown in the above-described embodiment. The magnetic thin film layer forming step was performed on the manufactured glass substrates 1G after performing the alkali treatment, and thus information recording media were manufactured. Similarly, treatment shown in Comparative Examples 1 and 2 was also performed.

[0060] (Working Example 1)

In Working Example 1, after "the second polishing step" was performed, the glass substrate was rinsed by being showered with hydrogen-rich water of 1.5 ppm for 3 minutes. Thereafter, the glass substrate was brought into contact with a sodium hydroxide solution at pH 10.5 for 5 minutes, and then was brought into contact with 0.1% ascorbic acid for 15 minutes. Then, the final cleaning was performed on the glass substrate using pure water.

[0061] (Working Example 2)

In Working Example 2, after "the second polishing step" was performed, the glass substrate 1G was rinsed by being showered with pure water. Thereafter, the glass substrate 1G was brought into contact with a sodium hydroxide solution at pH 10.5 for 5 minutes, and then was brought into contact with 0.1% ascorbic acid for 15 minutes. Then the glass substrate was cleaned using pure water.

[0062] (Working Example 3)

In Working Example 3, after "the second polishing step" was performed, the glass substrate was rinsed by being showered with hydrogen-rich water of 1.5 ppm for 3 minutes. Thereafter, the glass substrate was brought into contact with a sodium hydroxide solution at pH 10.5 for 5 minutes, and then the final cleaning was performed on the glass substrate using pure water. Then the glass substrate was cleaned using pure water.

[0063] (Comparative Example 1)

In Comparative Example 1, after "the second polishing step" was